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PATENT  
30205/38088

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of: Geun Su Lee et al.

Serial No.: 10/080,319

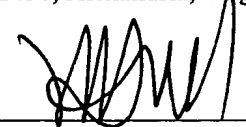
Filed: February 21, 2002

For: Photoresist Monomer, Polymer  
Thereof and Photoresist Composition  
Containing the Same

Group Art Unit: 1752

Examiner: Yvette C. Thornton

) I hereby certify that this paper and the  
) documents referred to as enclosed  
) therewith are being deposited with the  
) United States Postal Service as first class  
) mail, postage prepaid, on September 30,  
) 2004, in an envelope addressed to  
) Commissioner for Patents, P.O. Box  
) 1450, Alexandria, Virginia 22313-1450

  
\_\_\_\_\_  
Michael R. Hull  
Reg. No. 35,902  
Attorney for Applicants

COMMENT ON STATEMENT OF REASONS FOR ALLOWANCE

Commissioner for Patents  
P.O. Box 1450  
Alexandria, Virginia 22313-1450

Sir:

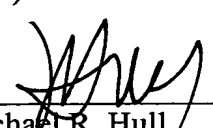
In addition to the reasons for allowance set forth in the allowance papers that were mailed in connection with the present application, it is respectfully submitted that the claims are allowable for the additional reasons that the invention defined by the language of the claims is neither anticipated by, nor would have been obvious when taken as a whole in view of, the art of record.

Respectfully submitted,

MARSHALL, GERSTEIN & BORUN LLP  
6300 Sears Tower  
233 South Wacker Drive  
Chicago, Illinois 60606-6357  
(312) 474-9577

September 30, 2004

By:

  
\_\_\_\_\_  
Michael R. Hull  
Reg. No. 35,902